IN THE CLAIMS:

Please cancel claims 28 and 35, and amend the claims as follows:

1-21. (Cancelled)

- 22. (Currently Amended) An apparatus for vaporizing a solid precursor, comprising:
- a housing having an inlet for receiving a carrier gas and an outlet in fluid communication with a sealable interior volume;

at least two surfaces comprising a mesh material contained in the housing having a solid chemical precursor applied thereto, wherein the solid chemical precursor includes a tantalum-containing precursor or a tungsten-containing precursor; and

- a heating member in thermal communication with contained within a wall of the housing, wherein at least one of the at least two surfaces is in thermal communication with the wall of the housing.
- 23. (Previously Presented) The apparatus of claim 22, wherein the at least two surfaces are spaced to allow passage of the carrier gas therebetween.
- 24. (Previously Presented) The apparatus of claim 22, wherein the at least two surfaces are formed of a material selected from the group consisting of stainless steel and ceramic.
- 25. (Previously Presented) The apparatus of claim 22, wherein the outlet is configured to operably couple to a reaction chamber of a deposition chamber.

- 26. (Previously Presented) The apparatus of claim 25, wherein the deposition chamber is selected from the group consisting of an ALD chamber, a CVD chamber, and an evaporative coating chamber.
- 27. (Previously Presented) The apparatus of claim 25, wherein the deposition chamber is an ALD chamber.
- 28. (Cancelled)
- 29. (Currently Amended) The apparatus of claim 22, wherein [[the]] <u>a</u> heating member is contained in one of the at least two surfaces.
- 30. (Previously Presented) The apparatus of claim 22, wherein one of the at least two surfaces is coupled to the housing.
- 31. (Previously Presented) The apparatus of claim 22, wherein the at least two surfaces have a form selected from the group consisting of an s-shape, a linear shape, and a cone shape.
- 32. (Currently Amended) An apparatus for vaporizing a solid precursor, comprising:
- a housing having an inlet for receiving a carrier gas and an outlet in fluid communication with a sealable interior volume;
- at least two cone shaped surfaces contained in the housing having a solid chemical precursor applied thereto; and

a heating member in thermal communication with contained within a wall of the housing, wherein at least one of the at least two surfaces is in thermal communication with the wall of the housing.

- 33. (Previously Presented) The apparatus of claim 32, wherein the at least two surfaces are spaced to allow passage of the carrier gas therebetween.
- 34. (Previously Presented) The apparatus of claim 32, wherein the at least two surfaces are formed of a material selected from the group consisting of stainless steel and ceramic.
- 35. (Cancelled)
- 36. (Currently Amended) The apparatus of claim 32, wherein [[the]] <u>a</u> heating member is contained in one of the at least two surfaces.
- 37. (Previously Presented) The apparatus of claim 32, wherein one of the at least two surfaces is coupled to the housing.
- 38. (Previously Presented) The apparatus of claim 32, wherein the solid chemical precursor includes a tantalum-containing precursor or a tungsten-containing precursor.